

Characterization of an Integrated Pt Counter Electrode on GaN/AlGaN-ISFET Wheatstone Bridge pH-sensors

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Summary:

GaN/AlGaN high electron mobility transistors (HEMT) were used as a pH-sensors, employing a Wheatstone bridge design in order to reduce parasitic effects on the sensor response. A Pt counter electrode was patterned directly on the sensor to achieve a more compact design and showed good operation characteristics. However, the signal stability was worse compared to an external counter electrode. In addition, we investigated the effect of different pH-sensitive gate layers, such as TiO₂ and Ta₂O₅, as well as the compensation of temperature effects and light-induced drift in the Wheatstone design.

Keywords: GaN/AlGaN, ISFET, Wheatstone Bridge, Heterostructure, pH-sensor

Introduction

Ion-sensitive field effect transistors (ISFETs) have attracted high research interest since their discovery by Bergveld in 1970 [1]. GaN/AlGaN HEMT structures have been demonstrated to exhibit excellent pH-sensor characteristics, such as a high, linear response, chemically inert surface and thus a small chemically induced drift [2]. However, these ISFETs also respond to other environmental parameters such as temperature or light and exhibit related signal drifts [3].

To reduce these effects, a Wheatstone bridge design was fabricated, consisting of one sensitive ISFET with the GaN gate exposed to the electrolyte FETs for which the gate was passivated by a 500 nm thick layer of sputter-deposited Al₂O₃. Thus, the latter ones do not show a pH response but are still affected by parasitic parameters. In addition, a Pt counter electrode was also processed on the chip to reduce the overall size of the sensor.

Methods

The Wheatstone bridges were fabricated on commercial wafers AlGaN/GaN HEMT structures (150 nm GaN/ 20 nm Al_{0.25}Ga_{0.75}N/ 3 nm GaN on HR-Si substrate, 2DEG charge density of > 8e12 cm⁻² and mobility of > 1800 cm²/Vs, supplied by soitec) with standard photolithographic methods. Heterostructures with and without 3 nm GaN cap were compared. A sketch of the sensor is depicted in Fig. 1.

The sensors were glued on a printed circuit board and the contacts were wire bonded to the

board. For measurement in electrolyte the contacts were covered with silicone glue. The measurements were performed with a three-electrode setup in a temperature-controlled beaker. The used electrolyte was phosphate-buffered saline (PBS 0.05 mM). For the pH-measurements titrations with diluted HCl were performed.

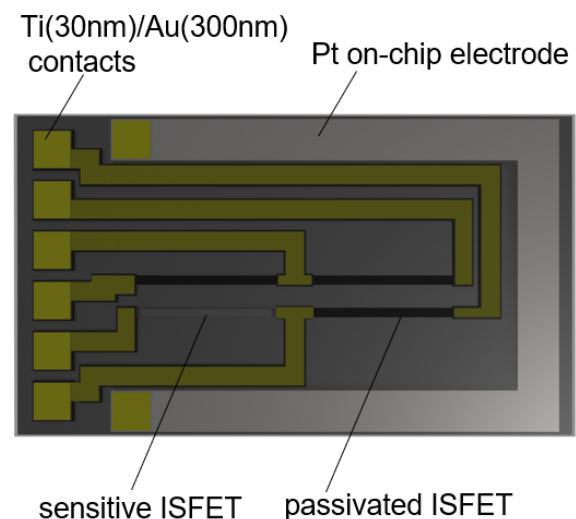


Fig. 1 Schematic of the device. The dimensions are 6 mm in length and 3.5 mm in width.

(1)

Results

To compare the on-chip electrode with an external counter electrode, pH-measurements with the sensitive ISFET only were performed. The drain-source current I_{DS} was regulated constant with the gate-source voltage V_{GS} . In Fig. 2. the measurement an external counter electrode is shown, Fig. 3 displays the results for the on-chip electrode. The sensors with an on-chip electrode exhibit a higher noise level, most likely due to the smaller distance to the gate, thus leading to a higher leakage current as it is also visible in the transfer characteristics.

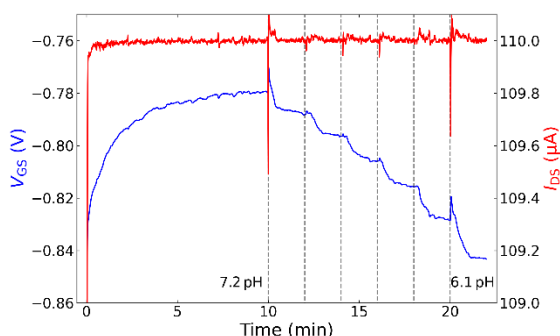


Fig. 2 pH-measurement with external counter electrode.

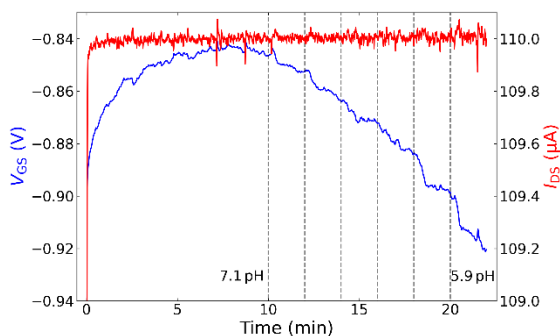


Fig. 3 pH-measurement with on-chip counter electrode.

A measurement with the on-chip electrode in the Wheatstone bridge configuration is depicted in Fig. 4. The bridge sensitivity of ≈ 2.5 mV/pH is similar to values reported in [4] (2.3 mV/pH).

Furthermore, temperature-dependent measurements were performed to analyse the compensation effects of the bridge and a significant reduction from 55 mV/°C to 7mV/°C. was found. Also, ultrathin coatings of the sensitive gate area with TiO_2 and Ta_2O_5 realized by Atomic Layer

Deposition were carried out and their effect on the sensor performance was studied.

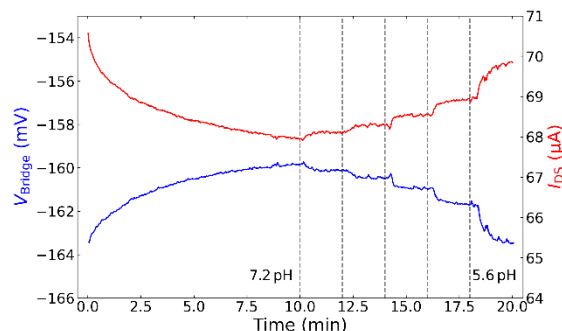


Fig. 4 pH-measurement in the Wheatstone Bridge configuration.

Perspective

The intention is to have a small and compact sensor. To add an on-chip reference electrode in addition would reduce the size of the sensor. Also, a combination of two different gate dielectrics on two sensitive ISFETs with differential read-out is a promising approach in that direction.

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References

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